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| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. M122-1098 | | PRIORITY SERIAL NO. 08/696,243 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT Klaus F. Schuegraf | | PRIORITY FILING DATE 08/13/96 | |
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| *Examiner Initial | | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
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| EXAMINER Erik/Kushin | | | | DATE CONSIDERED 6/14/00 | | | |
| *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | | |

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| | | Document Number | Date | Country | Class | Subclass | Translation |
| | | | | | | | Yes No |
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| EXAMINER <i>Erik Koster</i> | | | | DATE CONSIDERED <i>6/14/00</i> | | | |
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